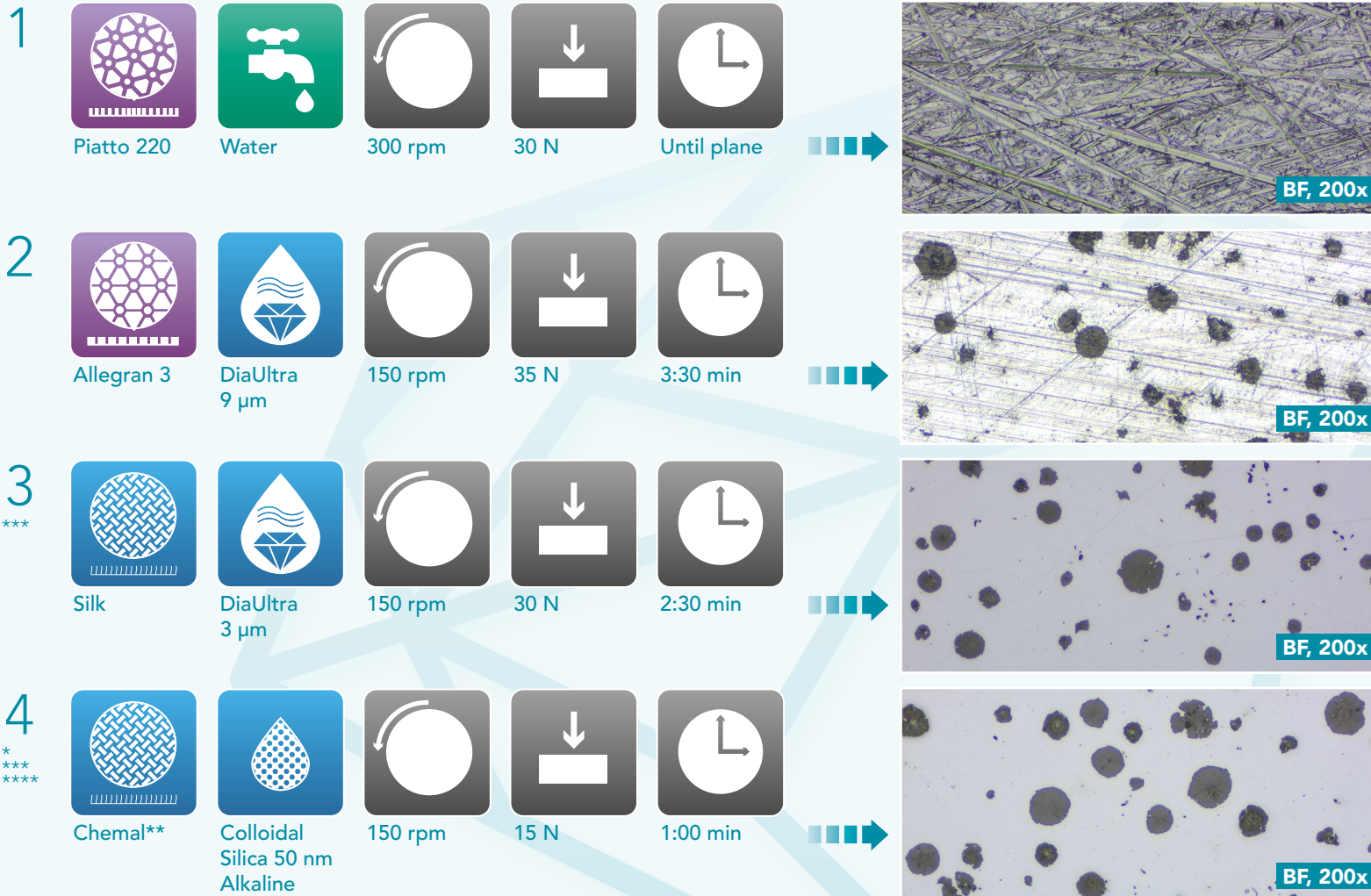


Aka-Brief #14 Cast Iron



Times are stated for a 300 mm preparation system and forces for an individual 40 mm dia. sample.

On a 250 mm system the times should be increased by 30%, on a 200 mm system by 100%.

With larger samples the force should be increased, with smaller samples decreased.

The rotational speed of the head (sample holder or sample mover plate) used is 150 rpm.

Time and force may vary depending on the equipment.

* Step 4 is optional.

** Prior to oxide polishing the polishing cloth should be wetted with water until the holder touches the polishing cloth.

For the last 10 seconds of the oxide polishing step, the polishing cloth should be flushed with water to clean both sample(s) and polishing cloth.

*** Oxide polishing gives a scratch free result but introduces some relief. To minimise relief, this step can be replaced by a final step using DiaUltra 1 µm on a Napal cloth.

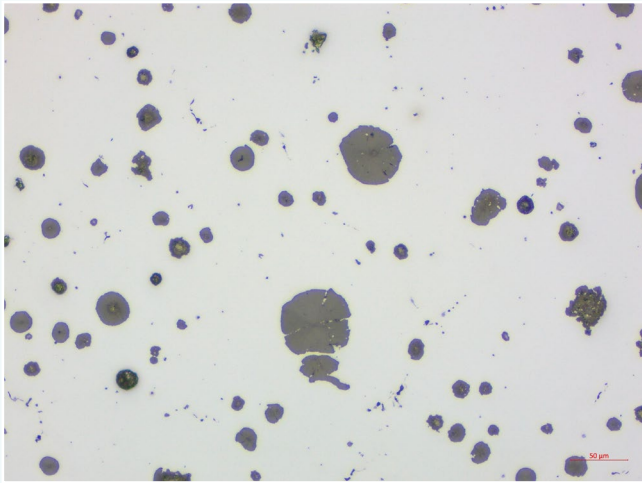
**** For water-sensitive samples, only diamond polishing is recommended using water-free suspensions/lubricants for the 3 and 1 µm steps. The use of water should also be avoided for cleaning after those preparation steps.

Please make sure that all necessary safety precautions are taken when handling chemicals.

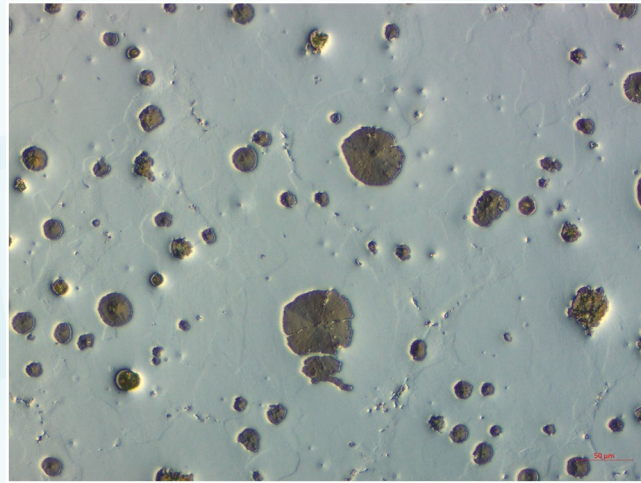


Aka-Brief #14 Cast Iron

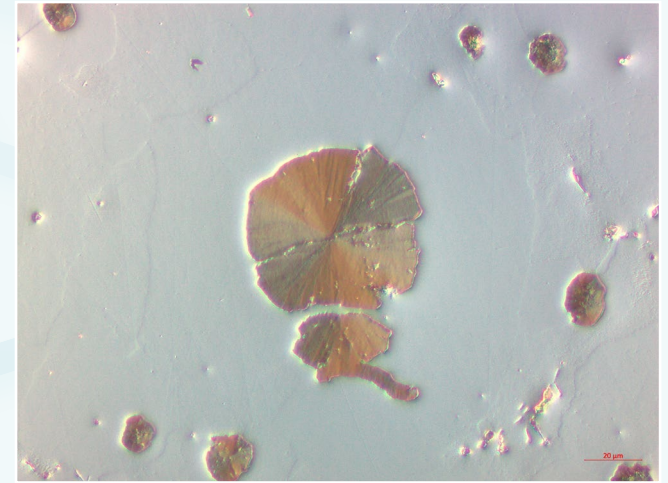
FINAL RESULT



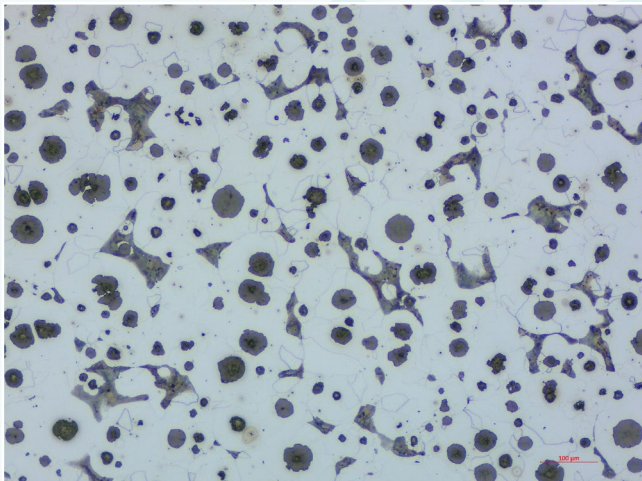
BF, 200x



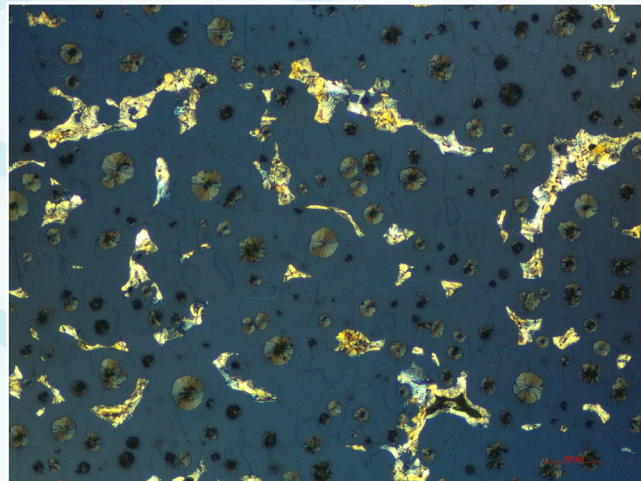
DIC, 200x



DIC, 500x



Etched with Nital 3%, BF, 200x



Etched with Nital 3%, POL, 200x